

XG0020

N-Channel Enhancement Mode SGT MOSFET

150V(VDS) / ± 20 V(VGS) / 200A(ID)

Rev0.5

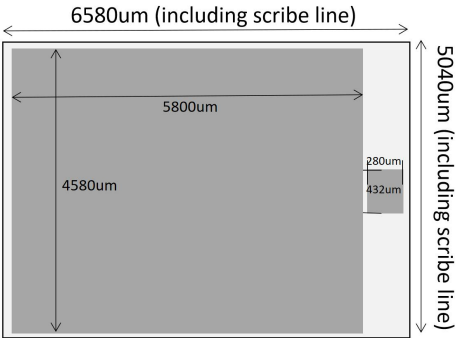
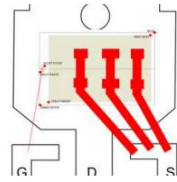


Wafer Specification

1. Order Information

Part No.	Description	Gross die / per 8" wafer
XG0020	150V(V_{DS}) / $\pm 20V(V_{GS})$/ 200A(I_D) N-Channel Enhancement Mode SGT MOSFET	813

2. Physical Characteristics

	Die Size: 6580 μ m $\times$ 5040 μ m (including scribe line)
	Gate: 280 μ m $\times$ 432 μ m
	For TO-263-3L package Suggest Bonding wire: Gate: 1 $\times$ 5 mil AL Source: 3 $\times$ 20 mil AL 

3. Mechanical Data

Nominal Back Metal Composition, Thickness	Ti-Ni-Ag (13kA°)
Nominal Front Metal Composition, Thickness	AlCu (4 μ m)
Wafer Diameter	200mm, with 010 notch
Wafer Thickness	200 μ m
Scribe Line Width	60 μ m

4. Key Electrical Characteristics of Die (at $T_J = 25^\circ\text{C}$, unless otherwise specified)S

Parameter	Description	Min.	Typ.	Max.	Unit	Test Conditions
V _(BR) DSS	Drain-to-Source Breakdown Voltage	150			V	V _{GS} =0V, I _D =250μA
I _D (Device Ref)	Continuous Drain Current			200	A	T _J =25°C
R _{DS(on)} (FT)	Static Drain-to-Source On-Resistance		3.7	4.6	mΩ	V _{GS} =10V, I _D =20A
V _{GS(th)}	Gate Threshold Voltage	2.2	3.2	4.2	V	V _{DS} =V _{GS} , I _D =250μA
I _{DSS}	Drain-to-Source Leakage Current			1	μA	V _{DS} =150V, V _{GS} =0V
I _{GSS}	Gate-to-Source Leakage Current			±100	nA	V _{GS} =±20V, V _{DS} =0V
R _g	Gate Poly Resistance		4.1		Ω	V _{DS} =0V, V _{GS} =0, f=1MHZ
C _{iss}	Input Capacitance		8600		pF	V _{DS} =75V, V _{GS} =0, f=1MHZ
C _{OSS}	Output Capacitance		770		pF	
C _{rss}	Reverse Transfer Capacitance		30		pF	
T _J , T _{STG}	Operating and Storage Temperature	-55°C to 150°C Max				